gas sensor with porous films of Bi₂Sr₂CaCu₂O_{8+x}: an analysis of the response

X.J. Huang a,1, J. Schoonman a, L.Q. Chen b

^a Laboratory for Inorganic Chemistry, Julianalaan 136, 2628 BL Delft, Netherlands
^b Institute of Physics, Academia Sinica, PO Box 603, Beijing 100080, China

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stract

A systematic investigation has been carried out on the time dependence of the response to NO and CO of a gas sensor that thick porous film of $Bi_2Sr_2CaCu_2O_{8+x}$ (BSCCO). The oxidation of reducing gases such as NO and CO by lattice oxygen cuts in parallel with desorption of NO_2 and CO_2 , respectively, in the whole range of temperatures investigated. An extension terported model has been proposed in order to describe the response of the sensor. The time dependence of the electrical sativity can be interpreted by assuming a conductivity dominated by Schottky barriers at grain boundaries. A kinetic model derlying the temperature dependence of the sensitivity to NO and the selectivity against CO is discussed. The high sensitivity NO as compared to that to CO is attributed to the high adsorption rate of NO at low temperatures. The good selectivity high temperatures is attributed to the rapid increase of the desorption rate of CO and/or CO_2 with increasing temperature. It response time increases with increasing equilibrium sensitivity S_0 . The recovery time decreases with increasing S_0 . They the decrease with increase of the desorption rate of $CO(NO_2)$.

gwords: BSCCO; Gas sensors

Introduction

The response behaviour of semiconductor gas sensors amot be predicted by calculations based on thermdynamic data. A power law has been used to describe to relation between the conductance and the constration of reducing gases for some semiconductor throws. Several models have been reported to interpret its relation [1–9]. Some researchers have studied the exponse behaviour of thin-film sensors with thickness than twice the Debye length [10–12]. Most of the exported studied present only experimental results and malitative interpretations.

The response of semiconductor gas sensors can be the to a surface oxidation or reduction process, including absorption of reducing species, electron exchange in smalled with oxygen exchange and desorption of a moduct. The investigation of the time dependence of the response is quite important to the understanding the mechanism of a sensor. The basic kinetic pa-

rameters can be evaluated through this analysis using a model. Insight into the basic parameters, such as sensitivity, selectivity, response and recovery times, may lead to improved sensors, but may also lead to unravelling of the mechanism of heterogeneous catalysis.

To the best of our knowledge, only Clifford [13] and Pizzini et al. [5] have studied the kinetic behaviour quantitatively. Their results indicated an exponential variation of resistance in time when an n-type semiconductor sensor was exposed to reducing gases in air. When an n-type semiconductor is exposed to reducing gases, the gases react with surface-adsorbed oxygen such as O^- and/or O_2^- , and this is a fast process. Therefore, it is difficult to analyse the response curve in detail [4].

We have shown in a previous paper [14] that a thick ($\approx 20~\mu m$) layer of $Bl_2Sr_2CaCu_2O_{8+x}$ (BSCCO) on an Al_2O_3 substrate exhibits sensitivity to NO in NO_x -air mixtures. The lattice oxygen atoms in the surface layer participate in the reaction process. This is a relatively slow process, the response and recovery times being relatively long.

In this work, the kinetic behaviour of the response processes of a sensor based on a thick film of p-

Present address: Group for Sensors and Solid State Ionics, Faculty (Technology, Christian-Albrechts University, Kaiserstrasse 2, D-MG Kiel, Germany.

conducting Bi₂Sr₂CaCu₂O_{8+x} with a 'Schottky-barrier-limited' conductance is analysed. When this sensor is exposed to a reducing gas, the adsorbed reducing gaseous species on the surface will react with a surface lattice oxygen, and subsequently desorbs. An equilibrium exists between the reducing gas, oxygen in the ambient and lattice oxygen in the surface layer. The concentration of lattice oxygens in the surface decreases. Therefore, the density of the electronic charge carriers, i.e., the holes, and hence the resistivity, will change.

An extension of the reported model will be used to describe the time dependence of the response and recovery of the sensor in reducing gases such as CO and NO. By making several assumption about the variables involved in the kinetic equations, a quasi-equilibrium approximation that predicts the response and recovery curves of the sensor is derived. The temperature dependence of the selectivity for NO against CO is discussed based on the kinetic data.

2. Theoretical considerations

In earlier reports [15], a sensing mechanism for the reducing gases CO and NO, or in general R, Bi₂Sr₂CaCu₂O_{8+x} was proposed. The mechanism involves the following steps:

$$ad + R \xrightarrow[k-1]{k_1} (R)_{ad}$$
 (1)

with ad an empty surface site, with an equilibrium constant $K_1 = k_1/k_{-1}$.

The interaction between $(R)_{ad}$ and a surface oxygen ion O_O^x is represented by

$$(R)_{ad} + O_O^x + 2h^* \xrightarrow{k_2} (RO)_{ad} + V_O^*$$
 (2)

(RO)_{ad} can desorb,

$$(RO)_{ad} \xrightarrow{k_3} RO(g) + ad$$
 (3)

Oxygen interact with the ceramic superconductor surface according to

$$\frac{1}{2}O_2 + ad \xrightarrow{k_4} O_{ad}$$
 (4)

$$O_{ad} + V_O^* \xrightarrow{k_5} O_O^x + 2h^*$$
 $O_O^x + 2h^*$ $O_O^x + 2h^*$ $O_O^x + 2h^*$ $O_O^x + 2h^*$ $O_O^x + 2h^*$

Eqs. (1) and (4) express the physical adsorption processes of the reducing gas R and O₂, respectively. They represent fast processes. Eq. (2) describes the oxidation of adsorbed species by lattice oxygen. Eqs. (3) and (5) represent product desorption and surface recovery processes, respectively.

The transition from physical adsorption to chemical adsorption of reducing gases (see Eq. (2)) is assumed to be a slow process and is the rate-determining step. [(RO)_{ad}] can be calculated by considering the equilibrium of this process.

In the present study, the low sintering temperature of the ceramic layer, i.e., the poorly sintered case, leads to 'Schottky-barrier' contacts [15], as schematically shown in Fig. 1. At the contact area a Schottky barrier arises due to charge trapped in the surface states. In this case, conductivity will be limited by charge transport across the barrier. The temperature dependence of this 'Schottky-barrier-limited' conductivity is given by

$$\sigma \approx \text{constant} \times \exp(-eV_s/kT)$$
 (6)

The conductivity activation energy is eV_s . The height variation of this barrier is ΔV_s , given by the Schottky equation for planar geometry, i.e.,

$$\Delta V_{s} = [Q_{s}^{2} - (Q_{s}^{0})^{2}]/2\epsilon\epsilon_{0}eN_{A}$$

$$= (2Q_{s}^{0}\Delta Q_{s} + \Delta Q_{s}^{2})/2\epsilon\epsilon_{0}eN_{A}$$
(7)

Here Q_s denotes surface charge, Q_s^0 denotes the surface charge in air and ΔQ_s is the change in surface charge due to adsorption of reducing gases. In this situation, $\Delta Q_s = 2nN_s[RO]_{ad}$ [16].

The time dependence of (RO)ad is given by

$$\frac{d[(RO)_{ad}]}{dt} = K_1 k_2 (O_O^x) [h^*]^2 P_R - k_{-2} [(RO)_{ad}] [V_O^*]$$
$$-k_3 [(RO)_{ad}]$$

The gases flow through the chamber continuously during the period of the measurements, and it is assumed that the concentration of the reactant is constant and that the product is removed instantaneously. The boundary conditions are

$$P_{\rm R}$$
 = constant (9)

Eq. (8) can be rewritten as

$$\frac{d[(RO)_{ad}]}{dt} = C_1 - C_2[(RO)_{ad}]$$
 (10)

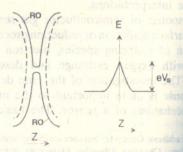


Fig. 1. Schematic of the 'Schottky-barrier-limited' contact.

$$\lfloor \sqrt{V_0} \rfloor + k_3$$
 (12)

 C_1 relates to the rate of chemisorption of a species and C_2 relates to the desorption rate

how partial pressures of reducing gases and at temperatures, the coverage of adsorbed molecules and hence the concentrations $[O_0^*]$, $[h^*]$ and the considered to be constant. Therefore, C_1 and the betaken as constant.

2 shows typical response and recovery curves. 1=0 the surface of a sensor is in equilibrium with The value of its resistivity in air is defined as the time. There is no chemical adsorption of the reducing $[(RO)_{ad}] = 0$. After a relatively long exposure time, rurface of the ceramic layer is in equilibrium with tax, hence $d[(RO)_{ad}]/dt = 0$ and $[(RO)_{ad}] = C_1/C_2$. The relatively long exposure time, and the ceramic layer is in equilibrium with tax, hence $d[(RO)_{ad}]/dt = 0$ and $[(RO)_{ad}] = C_1/C_2$. The relatively long exposure time, and taking the boundary within the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium with the second value of the ceramic layer is in equilibrium w

$$[0]_{id} = \frac{C_1}{C_2} - \frac{C_1}{C_2} \exp(-C_2 t)$$
 (13)

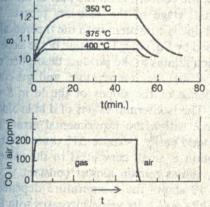
stituting Eq. (13) into Eq. (7), and considering that $\langle Q_s^0 \rangle$ and $\langle Q_s^0 \rangle = 2N_s[(RO)_{ad}]$ and $\langle Q_s^0 \rangle = 2N_s[(RO)_{ad}]$

$$V_1 = C \frac{C_1}{C_2} - C \frac{C_1}{C_2} \exp(-c_2 t)$$
 (14)

$$=N_sQ_s^0/\epsilon\epsilon_0eN_A \tag{15}$$

e sensitivity S is defined as

$$\frac{\rho}{a_{s}} = \frac{\sigma_{\text{air}}}{\sigma} = \exp(\Delta V_{s}/kT) \tag{16}$$



2 Typical response and recovery curves of a sensor.

with ρ and σ the resistivity and conductivity of the sensor when exposed to reducing gases, and $\rho_{\rm air}$ and $\sigma_{\rm air}$ the resistivity and conductivity of the sensor in air as a reference, respectively.

Combining Eqs. (14) and (16) yields

$$\ln S = \frac{1}{kT} \left[C \frac{C_1}{C_2} - C \frac{C_1}{C_2} \exp(-C_2 t) \right]$$
 (17)

The recovery process starts when the gas is replaced by air (i.e., Fig. 2) and is terminated when the resistivity of the sensor reaches the baseline value.

The partial pressure of the reducing gas become 0, and hence $(R)_{ad} = 0$. Eq. (10) can then be replaced by

$$\frac{\mathrm{d}[(\mathrm{RO})_{\mathrm{ad}}]}{\mathrm{d}t} = -C_2[(\mathrm{RO})_{\mathrm{ad}}] \tag{18}$$

At t=0 the boundary condition reads $[(RO)_{ad}] = C_1/C_2$; when the surface of the sensor has recovered its original state in air and the resistivity recovered its baseline, the boundary conditions are $[(RO)_{ad}] = 0$, and $d[(RO)_{ad}]/dt = 0$.

Integration of Eq. (18) using these boundary conditions yields (see Appendix 2)

$$[(RO)_{ad}] = \frac{C_1}{C_2} \exp(-C_2 t)$$
 (19)

$$\Delta V_s = C \frac{C_1}{C_2} \exp(-C_2 t) \tag{20}$$

$$\ln S = \frac{1}{kT} C \frac{C_1}{C_2} \exp(-C_2 t)$$
 (21)

The description of the recovery process is based on the hypothesis that the rate of reaction (5) is higher than that of the product desorption. The rational for this hypothesis will be discussed later in Section 4.1.

3. Experimental

The starting powder of Bi2Sr2CaCu2O8+x was prepared by the same method as described before [14]. Thick films were prepared by screen printing. Subsequently, the film was sintered at 600 °C in air for 20 h [15]. Ag paint was used to improve the electrical contact. The resistance of the sample was measured using a Keithley multimeter (847) and a Kipp & Zonen recorder (BD40). There is no obvious difference between the results of four-probe measurements and two-electrode measurements. This means that the contact resistance between the sample and Ag paste is much smaller than the resistance of the sample. The sample was exposed to gaseous ambients in a testing chamber that allows the gas flow to be controlled. The experimental set-up was described in more detail earlier [17]. The time dependence of the response of the sensor

upon exposure to and removal of NO and CO was measured in air at different temperatures.

4. Results and discussion

The resistivity of the sensor decreases with increasing temperature. It does not show bulk-limited behaviour because the ceramic material shows almost metallic conduction behaviour [17]. Instead, 'Schottky-barrier-limited' behaviour is observed [15].

4.1. Evaluation of the basic parameters of the response processes

4.1.1. The response process

From Eqs. (6), (7) and (10), and considering that $\Delta Q_s \ll Q_s^0$, one obtains

$$\frac{\mathrm{d}\ln S}{\mathrm{d}t} = \frac{1}{kT} \frac{\mathrm{d}(\Delta V_{\mathrm{s}})}{\mathrm{d}t} = C \frac{1}{kT} \frac{\mathrm{d}[(\mathrm{RO})_{\mathrm{ad}}]}{\mathrm{d}t}$$
$$= C \frac{1}{kT} (C_1 - C_2[(\mathrm{RO})_{\mathrm{ad}}]) \tag{22}$$

At t=0, $[(RO)_{ad}]=0$, and hence

$$\frac{\mathrm{d}\ln S}{\mathrm{d}t}\bigg|_{t\to 0} = \frac{C}{kT}C_1\tag{23}$$

In the initial stage, adsorbed R reacts on the surface with lattice oxygen. This causes a decrease of the hole concentration in the surface layer.

Combining Eqs. (11) and (23) yields

$$\frac{\mathrm{d}\ln S}{\mathrm{d}t}\bigg|_{t\to 0} = \frac{C}{kT}K_1k_2P_\mathrm{R}[\mathrm{O}_\mathrm{O}^\mathrm{x}][\mathrm{h}^*]^2 \tag{24}$$

Figs. 3 and 4 show the $\ln S$ versus time curve of NO and CO at different temperatures, respectively. The values of d $\ln S/dt$ ($t\rightarrow 0$) for NO or CO under different partial pressures and at different temperatures are evaluated from these Figures. Tables 1 and 2 list the numerical data.

Figs. 5 and 6 show the d ln S/dt $(t \rightarrow 0)$ versus P curves. They are straight lines, and this is consistent with the theoretical prediction expressed by Eq. (24). Their slopes are temperature dependent. The numerical values are listed in Tables 1 and 2, and represent $CeC_1/(kT)$. The value of C relates to the preparation conditions of the ceramic layer and temperature, and is independent of the nature of the gaseous species. The values of C_1 for different gaseous species can be evaluated from the values of these slopes.

From Eq. (11) it is predicted that C_1 is proportional to P_R when $[O_O^x]$ and $[h^*]$ are constant. Therefore, d In S/dt (t=0) is proportional to P_R .

Fig. 7 shows the temperature dependence of the slopes of the curves in Figs. 5 and 6. For both NO and

CO, the values of $CeC_1/(kT)$ hardly vary from 301 400 °C. When the temperature increases to 450 °C the value for NO decreases. The sensitivity to CO 450 °C is very low, so it is difficult to record the kine response curve. There are five parameters that determine the change with temperature, i.e. C, K_1 , $[O_0]$ as $[h^*]$ decrease with increasing temperature, while increases with temperature. It is quite difficult to it terpret the relation between the parameter values at the temperature. But at a fixed temperature, the value of C_1 for different gaseous species is proportional the slope. Their values for NO are higher than the for CO. The relation between C_1 and the sensitive and selectivity will be discussed later.

4.1.2. The recovery process

From Eq. (21) one obtains, taking the logarithm

$$\ln \ln S = \ln \left(\frac{C}{kT} \frac{C_1}{C_2} \right) - C_2 t \tag{6}$$

i.e., In In S should be proportional to the time.

Figs. 8 and 9 present ln ln S versus time curves h NO and CO, respectively. From Fig. 8(a) it is observed that the curves in the initial stage are straight line After a relatively long time, deviations from the strain lines occur. This can be attributed to oxygen diffusi in the material. During the response process, as the reducing gases adsorb on the surface, part of the latter oxygen in the sub-surface layer will diffuse to the surface layer due to a concentration gradient. This process slow. When the atmosphere is changed back to air, takes quite some time to recover the lattice oxygen the sub-surface layer, because the diffusion of one ions in Bi₂Sr₂CaCu₂O_{8+x} is rather slow at the operation temperature. The contribution of this process to total sensitivity is quite small though. Within the interfew minutes, the ln ln S versus time curves are strik lines. Eq. (21) cannot be used to interpret the recon process for long times.

Here, the concern is on the part of the curves dum the initial stage of the recovery process. The initial straight line is consistent with the theoretical prediction expressed by Eq. (21). The value of the slope represent C_2 , which relates to the product desorption rate. Take 3 and 4 list the temperature and gas-concentrated dependence of the slopes of the ln ln S versus the curves. The isothermal values of S ln ln S/S are almost the same within the experimental error. This can be understood easily, because S caused by reducing a adsorption is small compared to the value of S and S and S values remain almost constant.

Fig. 10 shows the temperature dependence of -1 ln ln S/dt (= C_2). Its value increases with temperature, which is reasonable as the desorption rate increase with increasing temperature. The values for 0 m

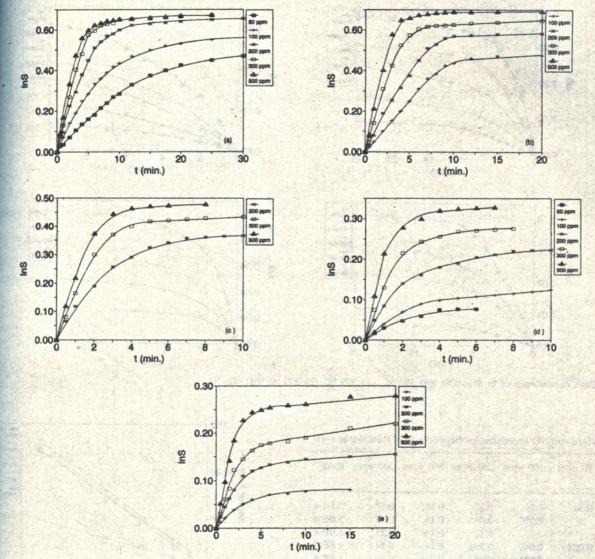


Fig. 3. Time dependence of in S to NO: (a) 300 °C, (b) 350 °C, (c) 375 °C, (d) 400 °C, (e) 450 °C.

higher than those for NO, especially at high temperatures.

It is also reasonable to assume that the rate of desorption, i.e., reaction (3) and its inverse reaction, is slower than oxygen incorporation, i.e., reaction (5). The former reaction is, therefore, the rate-determining step. Otherwise the value of C_2 will be gas independent.

4.2. Selectivity to NO against CO

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ity

From Eq. (17) it can be seen that after long equilibration times the reduced reaction

$$\ln S_0 = \frac{C}{kT} \frac{C_1}{C_2} \tag{26}$$

holds, where S_0 is the equilibrium sensitivity and $\ln S_0$ is proportional to $\exp(C_1/C_2)$.

From Tables 1 to 4, it can be concluded that the influence of temperature on C_1 is smaller than on C_2 . The C_2 value for CO increases much faster than that for NO. Table 5 lists the $(C_1)_{NO}/(C_1)_{CO}$ and $(C_2)_{NO}/(C_1)_{CO}$ $(C_2)_{CO}$ ratios at different temperatures. The values for $(C_1)_{NO}/(C_1)_{CO}$ are calculated from the values of the slopes of the curves in Figs. 3 and 4, which are listed in Tables 1 and 2. At low operating temperatures, the high sensitivity to NO is mainly attributed to the high C_1 value for NO. As the operating temperature increases, the sensitivity of CO will decrease quickly compared with than of NO; this is mainly attributed to the high C_2 value for CO. If the operating temperature increases, the selectivity for NO against CO will increase. However, the sensitivity will decrease. Therefore, there is an optimum temperature for practical utilization of the sensor.

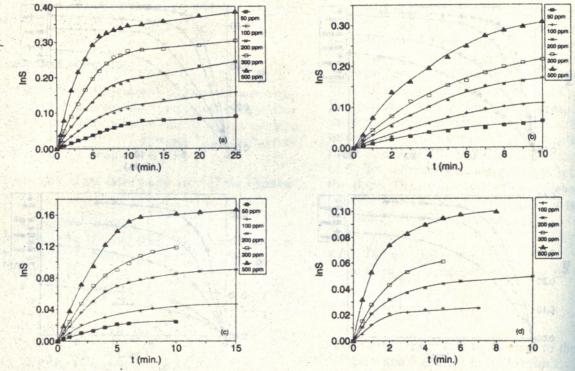


Fig. 4. Time dependence of In S to CO: (a) 300 °C, (b) 350 °C, (c) 375 °C, (d) 400 °C.

Table 1 Temperature and NO concentration dependence of d ln S/dt at $t \rightarrow 0$

Temperature and 140 concentration dependence of a in 5/42 at 1 · 0						
Temp.	50 ppm	100 ppm	200 ppm	300 ppm	500 ppm	dy/dP *
300	0.30	0.59	0.12	0.16	0.27	5.1E-4
350		0.050	0.095	0.16	0.24	5.0E-4
375			0.10	0.15	0.25	5.0E-4
400	0.023	0.045	0.093	0.14	0.24	4.8E-4
450		0.021	0.042	0.061	0.10	1.9E-4

^{*} dy/dP is the value of the slope of the curve of d ln S/dt at t=0 vs. the partial pressure of gas.

Table 2 Temperature and CO concentration dependence of d In S/dt at $t\rightarrow 0$

Temp. (°C)	50 ppm	100 ppm	200 ppm	300 ppm	500 ppm	dy/dP*
300	0.008	0.016	0.030	0.040	0.075	1.5E-4
350	0.011	0.025	0.035	0.048	0.068	1.3E-4
375	0.009	0.015	0.029	0.042	0.075	1.5E-4
400	BULLINGS	0.013	0.028	0.41	0.065	1.4E-4

^{*} dy/dP is the value of the slope of the curve of d ln S/dt at t=0 vs. the partial pressure of gas.

4.3. Response time

The response time t_r is defined as the time required for the sensor signal to reach a specified fraction α of the equilibrium value on exposure to the gases [6]. If the sensitivity is S_1 at time t_r , and the equilibrium

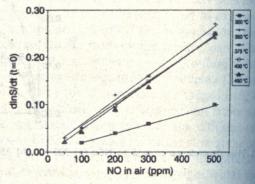


Fig. 5. NO partial-pressure dependence of the slopes of the plot of $\ln S$ vs. time at t=0.

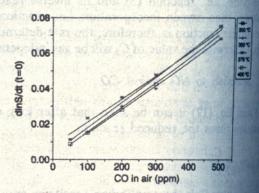
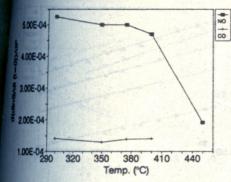


Fig. 6. CO partial-pressure dependence of the slopes of the plots of $\ln S$ vs. time at t=0.



Temperature dependence of the slope of the curves in Figs.

sitivity at
$$t = \infty$$
 is S_0 , then

$$-1=a(S_0-1)$$
 (27)

 t_a =90%, t_r is defined as the 90% response time. t_r can be expressed as

$$S_1 = \alpha S_0 + (1 - \alpha) \tag{28}$$

$$\ln S_1 - \ln S_0$$
 can be expressed as

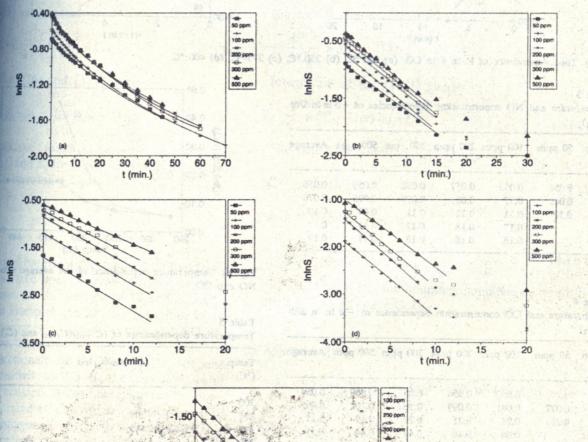
$$\ln S_1 - \ln S_0 = \ln \left[\alpha S_0 + (1 - \alpha) \right] - \ln S_0 \tag{29}$$

$$\ln S_1 - \ln S_0 = \frac{1}{kT} C \frac{C_1}{C_2} \exp(-C_2 t_1)$$
 (30)

From Eqs. (26) and (30) one obtains

$$t_{\rm r} = \frac{1}{C_2} \left\{ \ln \left(\frac{1}{kT} C \frac{C_1}{C_2} \right) - \ln[\ln S_0 - \ln(1 - \alpha + \alpha S_0)] \right\}$$

$$= \frac{1}{C_2} \{ \ln \ln S_0 - \ln[\ln S_0 - \ln(1 - \alpha + \alpha S_0)] \}$$
 (31)



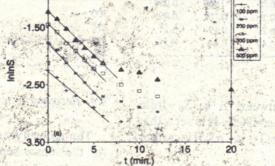


Fig. 8. Time dependence of In In S to NO: (a) 300 °C, (b) 350 °C, (c) 375 °C, (d) 400 °C, (e) 500 °C.

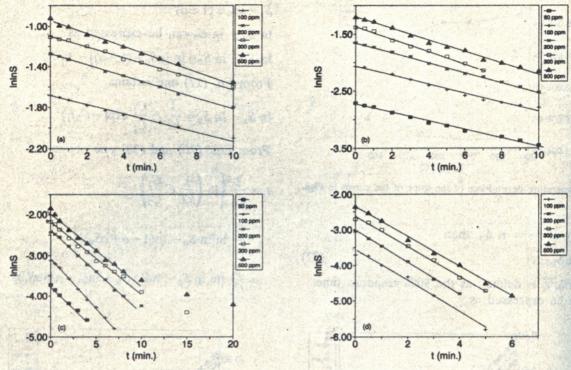


Fig. 9. Time dependence of ln ln S to CO: (a) 300 °C, (b) 350 °C, (c) 375 °C, (d) 400 °C.

Table 3
Temperature and NO concentration dependencies of $-d \ln \ln S/dt$ (= C_2)

Temp.	50 ppm	100 ppm	200 ppm	300 ppm	500 ppm	Average
300	0.051	0.053	0.057	0.058	0.059	0.056
350	0.069	0.77	0.08	0.079	0.075	0.076
375	0.10	0.11	0.11	0.11	0.09	0.10
400	0.838	0.17	0.18	0.17	0.14	0.17
450	The same	0.16	0.18	0.18	0.17	0.17

Table 4
Temperature and CO concentration dependence of $-d \ln \ln S/dt$ $(-C_2)$

Temp.	50 ppm	100 ppm	200 ppm	300 ppm	500 ppm	Average
300		0.050	0.056	0.051	0.060	0.054
350	0.077	0.081	0.099	0.107	0.101	0.093
375	0.21	0.24	0.21	0.20	0.19	0.21
400		0.46	0.48	0.40	0.44	0.45

Fig. 11 shows the relation between $\ln \ln S_0 - \ln[\ln S_0 - \ln(1 - \alpha + \alpha S_0)]$ and S_0 with $\alpha = 90\%$. It is seen that the value of $\ln \ln S_0 - \ln[\ln S_0 - \ln(1 - \alpha + \alpha S_0)]$ increases with S_0 .

Hence, the response time increases with increasing S_0 and decreases with increasing value of C_2 .

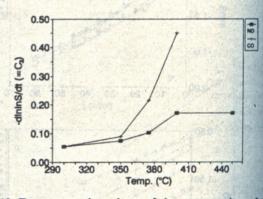


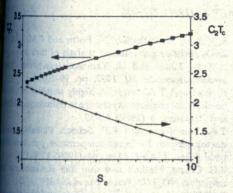
Fig. 10. Temperature dependence of the average values of C_1 in NO and CO.

Table 5 Temperature dependencies of $(C_1)_{NO}/(C_1)_{CO}$ and $(C_2)_{NO}/(C_2)_{CO}$

Temp. (°C)	$(C_1)_{NO}/(C_1)_{CO}$	$(C_2)_{NO}/(C_2)_{CO}$	
300	3.5	1.0	
350	3.9	0.82	
375	3.5	0.50	
400	3.4	0.37	

4.4. Recovery time

The recovery time t_c is defined as the time required for the sensor sensitivity to drop from the equilibrium value to a specific value S_2 on exposure to inert gas [6]. S_2 is related to S_0 :



Larves of $\ln \ln S_0 - \ln[\ln S_0 - \ln(1 - \alpha + \alpha S_0)] = C_2 t_r$ and $\frac{1}{2} \ln \ln[1 + \beta(S_0 - 1)] = C_2 t_c$ vs. S_0 .

$$I=\beta(S_0-1) \tag{32}$$

=10%, t_c is the 90% recovery time. In Eq. (32), S_2 can be expressed as

$$1+\beta(S_0-1) \tag{33}$$

Eq. (21) one obtains

$$-\ln S_0 = C \frac{1}{kT} \frac{C_1}{C_2} \exp(-C_2 t_c)$$
 (34)

bining Eqs. (26) and (34) yields

$$\frac{1}{6} \ln \ln S_0 - \ln \ln[1 + \beta(S_0 - 1)]$$
 (35)

Il shows the relation between $\ln \ln S_0 - \ln \beta(S_0 - 1)$ and S_0 for $\beta = 10\%$. The recovery time taxes with increasing C_2 and S_0 .

Conclusions

interior model based on the assumption that lattice in the surface layer is involved in the oxidation aloring gases on the surface of Bi₂Sr₂CaCu₂O_{8+x} be used to interpret the kinetic behaviour of the case and recovery processes to NO and CO of a set based on this material.

he kinetic rationale of the temperature dependence of the sensitivity to NO and the selectivity against has been discussed. As the temperature increases, table of parameter C_1 , which relates to the admin rate, changes slowly. Both desorption rates of and CO increase, but that for CO increases more

is difficult to clarify the temperature dependence is sensitivity. The high sensitivity to NO compared that to CO at low operating temperatures is mainly divided to the high adsorption rate of NO. The good staticy at high temperatures is attributed to the increase of the desorption rate of CO and/or lat increasing temperatures.

The response time increases with increasing S_0 and the recovery time decreases with increasing S_0 . They both decrease with the desorption rate of R and RO.

Appendix 1

Eq. (13) will be derived starting Eq. (10):

$$\frac{\mathrm{d}x}{\mathrm{d}t} = C_1 - C_2 x \tag{A1.1}$$

with boundary conditions

$$x|_{t=0} = 0$$
 (A1.2)

$$x|_{t=\infty} = \frac{C_1}{C_2}$$
 (A1.3)

$$\frac{\mathrm{d}x}{\mathrm{d}t}\bigg|_{t=\infty} = 0 \tag{A1.4}$$

Eq. (A1.1) can be rewritten as

$$\frac{\mathrm{d}x}{C_1 - C_2 x} = \mathrm{d}t \tag{A1.5}$$

Integration of Eq. (A1.5) yields

$$-\frac{1}{C_2}\ln(C_1-C_2x)=t+C$$
 (A1.6)

The boundary condition (A1.2) reveals

$$C = \frac{1}{C_2} \ln C_1 \tag{A1.7}$$

and, therefore, x reads

$$x = \frac{C_1}{C_2} - \frac{C_1}{C_2} \exp(-C_2 t)$$
 (A1.8)

Eq. (A1.8) satisfies the boundary conditions expressed in Eqs. (A1.3) and (A1.4).

Appendix 2

Eqs. (19)-(21) will be derived starting from Eq. (18):

$$\frac{\mathrm{d}x}{\mathrm{d}t} = -C_2 x \tag{A2.1}$$

with boundary conditions

$$x|_{t=0} = \frac{C_1}{C_2} \tag{A2.2}$$

$$x|_{t=\infty} = 0 \tag{A2.3}$$

$$\frac{\mathrm{d}x}{\mathrm{d}t} = 0 \tag{A2.4}$$

Eq. (A2.1) can be rewritten as

$$\frac{\mathrm{d}x}{-C_2x} = \mathrm{d}t \tag{A2.5}$$

Integration of Eq. (A2.5) yields

$$-\frac{1}{C_2} \ln x = t + C$$
 (A2.6)

The boundary condition (A2.2) reveals

$$C = -\frac{1}{C_2} \ln \left(\frac{C_1}{C_2} \right) \tag{A2.7}$$

and, hence, x reads

$$x = \frac{C_1}{C_2} \exp(-C_2 t)$$
 (A2.8)

Eq. (A2.8) satisfies the boundary conditions expressed in Eqs. (A2.3) and (A2.4).

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